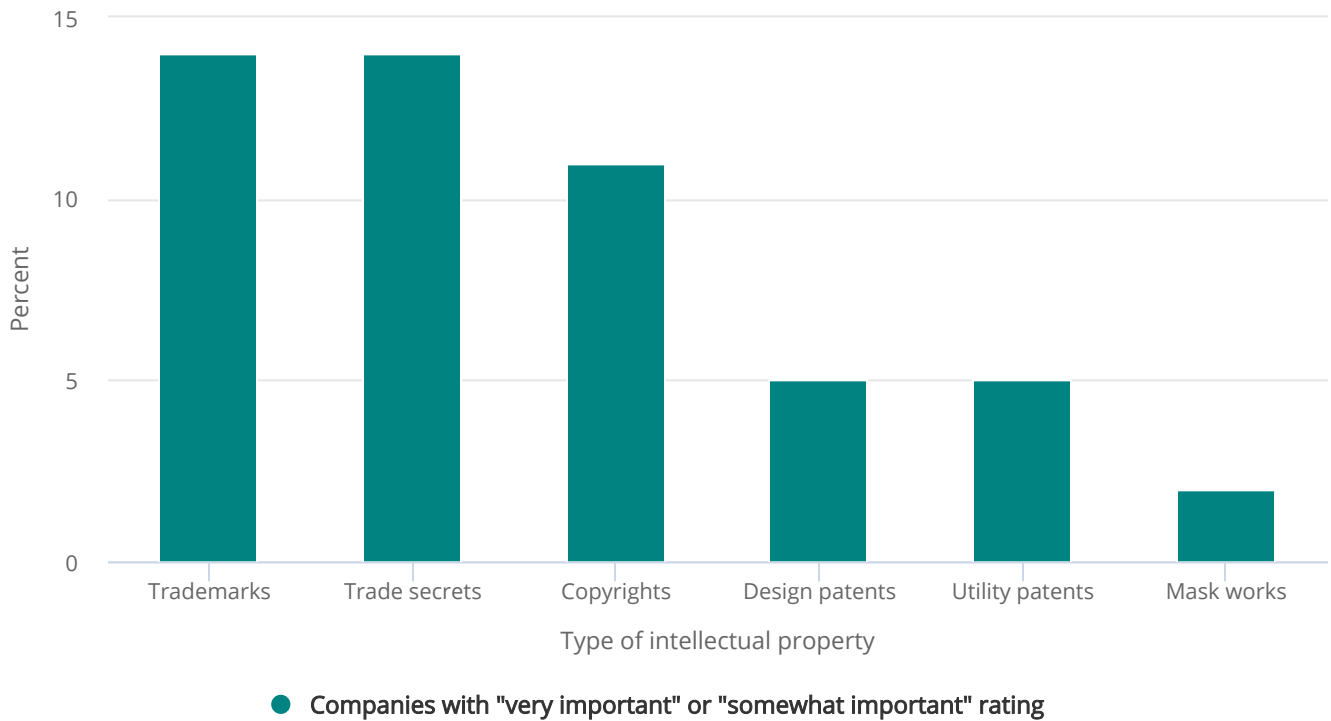


FIGURE 8-1

For companies that performed or funded R&D, shares rating intellectual property as being very or somewhat important: 2011



**Note(s)**

A mask work is a two- or three-dimensional layout or topography of an integrated circuit on a semiconductor that is protected under U.S. intellectual property law.

**Source(s)**

National Science Foundation, National Center for Science and Engineering Statistics, Business R&D and Innovation Survey (BRDIS), 2011.

*Science and Engineering Indicators 2018*